

ABSTRACT

To provide a resist which is excellent in the solubility in a resist solvent and little dependent on baking temperature and can form developed patterns reduced in line edge roughness. An acrylic polymer characterized by comprising units of the general formula (1), units of general formula (2), and units of general formula (3) and/or units of general formula (4), wherein R, R', R'' and R''' are each hydrogen, methyl, or trifluoromethyl; R¹ is hydrogen, C₁₋₄ linear or branched alkyl, alkoxy, or C₁₋₄ linear or branched fluoroalkyl; X is a C₇₋₂₀ polycyclic aliphatic hydrocarbon group consisting of carbon atoms and hydrogen atoms; R² and R³ are each independently C₁₋₄ linear or branched alkyl; R⁴ is a C₄₋₂₀ alicyclic hydrocarbon group; R⁵ is C₁₋₄ linear or branched alkyl; and R⁶ and R⁷ are each hydrogen or C₁₋₄ linear or branched alkyl.

